



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

111Re 3
S. Steptoe
3-17-03

In re the Application of: **HASHIMOTO, Hiroshi et al.**

Group Art Unit: 2714

Serial No.: **09/960,399**

Examiner: **Howard Weiss**

Filed: **September 24, 2001**

P.T.O. Confirmation No.: **5652**

For. **SEMICONDUCTOR INTEGRATED CIRCUIT AND FABRICATION PROCESS
THEREOF**

PRELIMINARY AMENDMENT

Commissioner for Patents
Washington, D.C. 20231

Date: March 5, 2003

Sir:

In response to the Office Action dated December 11, 2002, please amend the above-identified patent application as follows:

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IN THE CLAIMS:

Technology Center 2600

Cancel claim 17 without prejudice or disclaimer.

Amend claim 16 as follows:

16. (Amended) A semiconductor integrated circuit, comprising:

a semiconductor substrate;

B1 Cont a non-volatile memory formed in a memory cell region of said semiconductor substrate;

a first MOS transistor formed on a first device region of said semiconductor substrate, said first MOS transistor having a first gate insulation film of first thickness and a first gate electrode;

a second MOS transistor formed on a second device region of said semiconductor substrate, said second MOS transistor having a second gate oxide film of second thickness and a second gate